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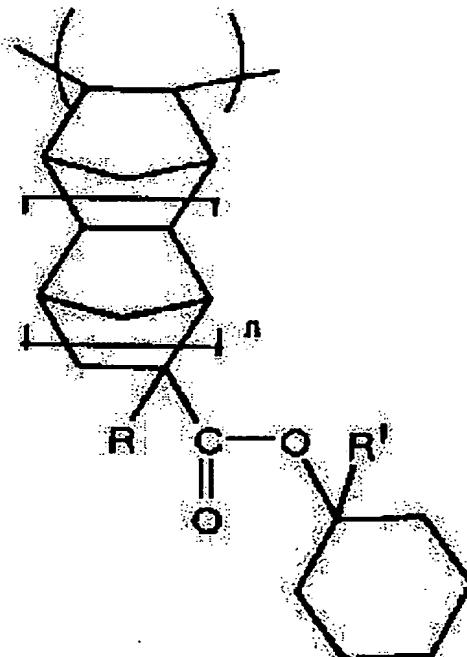
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(54) POSITIVE TYPE RESIST COMPOSITION AND ACID DISSOCIABLE GROUP-CONTAINING MONOMER USED IN SAME

(57)Abstract:

PROBLEM TO BE SOLVED: To obtain a low-cost positive type resist composition for ArF excellent in sensitivity, resolution and electron beam resistance by incorporating a specified polymer and a compound that generates an acid when irradiated with radiation.

SOLUTION: The resist composition contains a polymer containing at least units of the formula and a compound that generates an acid when irradiated with radiation. In the formula, R is H or a lower alkyl, R₁ is a ≥2C alkyl and (n) is 0 or 1. The units of the formula are derived from a polycyclic olefin such as bicyclo[2,2,1]-2-heptene (norbornene) or tetracyclo[4,4,0,12.5,17.10]-3-dodecene and the polymer contains the units in the principal chain and has a 1-≥2C alkyl-1-cyclohexyloxycarbonyl group in the 5- or 8-position on each ring. The resist composition forms a resist pattern excellent in dry etching resistance without using an expensive polycyclic hydrocarbon group at the acid dissociable group part.



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